Contents lists available at ScienceDirect

### Journal of Alloys and Compounds

journal homepage: http://www.elsevier.com/locate/jalcom

# Fabrication of *L*1<sub>0</sub>-FeNi phase by sputtering with rapid thermal annealing

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#### A R T I C L E I N F O

Article history: Received 9 May 2017 Received in revised form 24 February 2018 Accepted 26 February 2018

Keywords: L1<sub>0</sub>-FeNi Ordered alloys Magnetic materials Magnetic anisotropy Sputtering

#### ABSTRACT

FeNi films were directly deposited on MgO(001) substrates by co-sputtering and rapid thermal annealing (RTA). The formation of the  $L_{10}$  phase was investigated for films with different thicknesses and different annealing conditions by grazing incidence X-ray diffraction. For the FeNi films with a thickness of 5 nm, superlattice 001 and 110 peaks were observed after annealing at a heating rate of 50 °C/s, which indicates that three variants of  $L_{10}$  grains were formed in the films. The maximum long-range order parameter, which corresponded to a volume-averaged parameter, was approximately 0.11. For the FeNi films with a thickness of 30 nm, a superlattice 110 peak was only observed after annealing at a heating rate of 50 °C/s, and the formation of 001 textured grains was clarified. Magnetic properties also changed depending on the FeNi film structures. The formation mechanism of  $L_{10}$ -FeNi is discussed based on the strain caused by RTA in the FeNi films.

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#### 1. Introduction

For a perpendicular recording media and motor magnets, materials with large uniaxial magnetic anisotropy  $(K_{ii})$  are necessary and investigated for several materials [1–4]. *L*1<sub>0</sub>-ordered alloys, such as  $L_{10}$ -FePt and  $L_{10}$ -FePd, are known to reveal large  $K_{11}$  [5–7]. Therefore, these alloys are promising for high-density perpendicular recording media or high-maximum-energy magnets. Although many L10-ordered alloys include a noble element, leading to a high cost for industrial products, L10-FeNi includes only low-cost elements and exhibits large saturation magnetization ( $M_s$ ; 1200–1300 emu/cc) and  $K_u$  (1.3 × 10<sup>7</sup> erg/cc), excellent corrosion resistance, and high Curie temperature [8-11]. In other words, this material is a "noble-element-free and large  $K_u$  material". From previous studies [12–14] involving L10-FeNi film experiments, it was found that  $K_u$  increased with the order parameter (S) and was induced by the spin-orbit coupling of Fe 3d electrons in the  $L1_0$  structure. However, the formation of the *L*1<sub>0</sub>-FeNi phase is quite difficult with conventional methods such as annealing. Because the orderdisorder transition temperature (~320 °C) is too low compared to tween the  $L1_0$  and A1 phases is also small [15-18], therefore, the ordering process hardly occurs. In nature,  $L1_0$ -FeNi is found in ironmeteorites [10,11,18-20]; experimentally it was obtained using special techniques such as neutron irradiation in the applied magnetic field [8,9], and the films were fabricated by molecular beam epitaxy (MBE) on a buffer layer with good lattice match to  $L1_0$ -FeNi [12,14,21-24]. Recently, the formation of an  $L1_0$ -FeNi alloy was also reported when using layer-by-layer sputtering deposition [25] or various alloying methods [26-29]; however, the volume fraction of  $L1_0$ -FeNi was small. In this paper, we fabricated  $L1_0$ -FeNi films on MgO(001) sub-strates by conventional sputtering and rapid thermal annealing

the melting point (>1400 °C), the formation-energy difference be-

strates by conventional sputtering and rapid thermal annealing (RTA). In certain cases, the RTA method is effective in enhancing the  $L_{10}$  ordering process; [001] textured  $L_{10}$ -FePt and CoPt films were easily obtained on polycrystalline substrates [30–33]. Here, the relation between annealing conditions and structural and magnetic properties for the FeNi films including  $L_{10}$ -FeNi phase were systematically investigated.

#### 2. Experimental procedures

All FeNi films were prepared by co-sputtering of Fe (RF) and Ni (DC) directly onto clean MgO(001) substrates at room temperature







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using an ultra-high vacuum (base pressure:  $< 3 \times 10^{-6}$  Pa) magnetron sputtering system [34]. Sputtering powers of the Fe and Ni targets were 31 and 11 W, respectively. The Ar gas pressure during sputtering was 0.2 Pa, and the co-deposition rate was 0.015 nm/s. The total thicknesses of the co-deposited FeNi films were 5, 30, 50, and 100 nm. The composition of FeNi was estimated to be Fe<sub>47</sub>Ni<sub>53</sub> (at.%) from electron probe microscopy analysis. After deposition, the FeNi films were annealed by using an RTA system consisting of an infrared light source and a vacuum chamber (starting pressure:  $< 5 \times 10^{-4}$  Pa). The annealing conditions, such as an annealing temperature (250-400 °C) and annealing time (5-20 h), were used. To study the effect of heating rate on the formation of  $L1_0$ -FeNi phase, it was changed from 0.1 °C/s to 50 °C/s. The RTA method involves a rapid heating rate  $(50 \circ C/s)$  followed by holding the temperature constant. The typical heating rate was 0.1 °C/s and followed by holding the temperature constant for thermal annealing (TA). For structural characterization, grazing incidence X-ray diffraction (GI-XRD) measurements were carried out with an in-plane scan ( $\varphi$ -2 $\theta$ , where  $\varphi$  is the rotation angle of the sample, and  $2\theta$  is the detector position) using synchrotron radiation at the synchrotron radiation facility of SPring-8 (BL46XU). The incident angle of the X-ray beam was 0.28° with the film surface, and samples were enclosed in a He-gas-exchange chamber to reduce the background due to scattering from air. To use anomalous dispersion, X-ray energy was chosen near the Fe-K absorption edge (about 7.110 keV) because the superlattice peak intensity should be enhanced at the Fe-K absorption edge compared to that at offresonance energies. The S was evaluated with the following Equation:

$$S = \sqrt{\frac{\left(I_{sup} / I_{fund}\right)^{exp}}{\left(I_{sup} / I_{fund}\right)^{cal}_{S=1}}},$$
(1)

where  $I_{sup}$  and  $I_{fund}$  are integrated intensities in the GI-XRD measurement for the superlattice and fundamental peaks, respectively. The superscript of "*exp*" means the experimentally observed value estimated by peak-fitting using a pseudo-Voigt function, and "*cal*" means the theoretical value with the perfect order (S = 1) calculated with the following Equation:

$$I = |F|^2 \frac{1}{\sin 2\theta},\tag{2}$$

where *F* is the structure factor, and  $1/\sin 2\theta$  is the Lorentz factor.  $|F|^2$  is described with the following Equation:

$$|F|^{2} = 4 \left\{ \left\{ \left( f_{0Fe} + f_{Fe}'(\varepsilon) \right) e^{-M_{Fe}} \pm \left( f_{0Ni} + f_{Ni}'(\varepsilon) \right) e^{-M_{Ni}} \right\}^{2} + \left\{ f_{Fe}^{''}(\varepsilon) e^{-M_{Fe}} \pm f_{Ni}^{''}(\varepsilon) e^{-M_{Ni}} \right\}^{2} \right\},$$
(3)

where  $f_{0\text{Fe}}$  and  $f_{0\text{Ni}}$  are the normal atomic scattering factors of Fe and Ni [35], and  $e^{-M}_{Fe}$  and  $e^{-M}_{Ni}$  are the Debye-Waller factors [36] of Fe and Ni, respectively. In this study, X-ray energy was adjusted to 7.11 keV (Fe-K adsorption edge); therefore, the anomalous dispersion effect was taking place, and f' and f'' are the real and imaginary parts of anomalous scattering factors, respectively. Our measurements required neither adsorption correction nor polarization correction, because in-plane geometry and incident X-rays with linearly polarized light were used. In addition, high-resolution transmission electron microscopy (HRTEM) observation was used for the microstructural analysis of FeNi films. Cross-sectional images were observed with electron beam//MgO[100] direction. Magnetization curves were measured by a superconducting quantum interference device (SQUID) at room temperature. Magnetic fields up to  $\pm 20$  kOe were applied along the parallel and perpendicular directions to the plane.

#### 3. Results

#### 3.1. Annealing time dependence for FeNi films (5 nm)

Fig. 1(a) shows GI-XRD profiles for an FeNi film (5 nm) annealed at 350 °C at a heating rate of 50 °C/s and held for 20 h. The incident directions of the X-ray beam are related to the scattering vector (**K**) along the MgO [100] or [110], the results of which are shown with broken and solid lines, respectively. In the profile for the K//MgO [110] direction, superlattice 110 and fundamental 220 peaks were observed. This orientation relationship indicates that the [001] axis (i.e., c-axis) is perpendicular to the MgO(001) substrate. On the other hand, in the profile with the K//MgO[100] direction, superlattice 001 and fundamental 200 peaks were observed. With inplane XRD measurement, observation of diffraction from (100) planes is possible; however, for the  $L1_0$  structure, a 100 peak should not be observed due to its structural symmetry [5]. Thus, this peak was indicated as 001 in the profile instead of the 100 peak. This orientation relationship indicates that the [001] axis (i.e., c-axis) for L10-FeNi is parallel to the MgO(001) substrate. Therefore, both superlattice diffraction peaks confirm the formation of two variants of the  $L1_0$ -FeNi films, that is, the *c*-axis is perpendicular and parallel to the film plane. In general, an *L*1<sub>0</sub>-ordered alloy with high tetragonality is easily formed because RTA induces tensile strain to the



Fig. 1. (a) GI-XRD profiles for FeNi film (5 nm) on MgO(001) substrates annealed at 350 °C at a heating rate of 50 °C/s for 5–20 h. (b) Profiles in a narrow range around FeNi(001) and (200) peaks. (c) Profiles in a narrow range around FeNi(110) and (220) peaks.

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